

ABSTRACT

An object of the present disclosure is to provide a sputtering target that has improved conductivity and, for example, improves productivity in forming a film using a DC sputtering device. The sputtering target of the present disclosure includes: an aluminum matrix; and (1) a material or phase containing aluminum and further containing either a rare earth element or a titanium group element or both a rare earth element and a titanium group element or (2) a material or phase containing either a rare earth element or a titanium group element or both a rare earth element and a titanium group element, at a content of 10 to 70 mol% in the aluminum matrix.